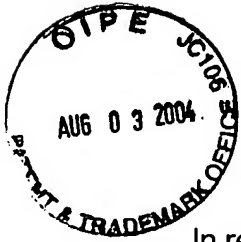


IFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Chen et al.

Docket No.: TI-35022.1

Serial No.: 10/719,280

Art Unit: 2813

Filed: 11/21/03

Examiner: Chen, Jack S J

Title: Use Of Hafnium Silicon Oxynitride As The Cap Layer Of The Sidewall
Spacer

AMENDMENT UNDER 37 C.F.R. §1.111

July 30, 2004

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Commissioner:

MAILING CERTIFICATE UNDER 37 C.F.R. §1.8(A)

I hereby certify that the above correspondence is being deposited
with the U.S. Postal Service on 7-30-04
as First Class Mail in an envelope addressed to: Commissioner for
Patents, P.O. Box 1450, Alexandria, VA 22313-1450

Karen Vertz 7-30-04
Karen Vertz Date

In response to the Office Action, dated 5/20/2004, in the above-identified patent application, please make the following amendments. They are respectfully submitted as a full and complete response to that Action. Charge any required fees to the deposit account of Texas Instruments Incorporated, Account No. 20-0668.